

Volume 22 (2015)

Supporting information for article:

Tuning the phase transition of ZnO thin films through lithography: an integrated bottom-up and top-down processing

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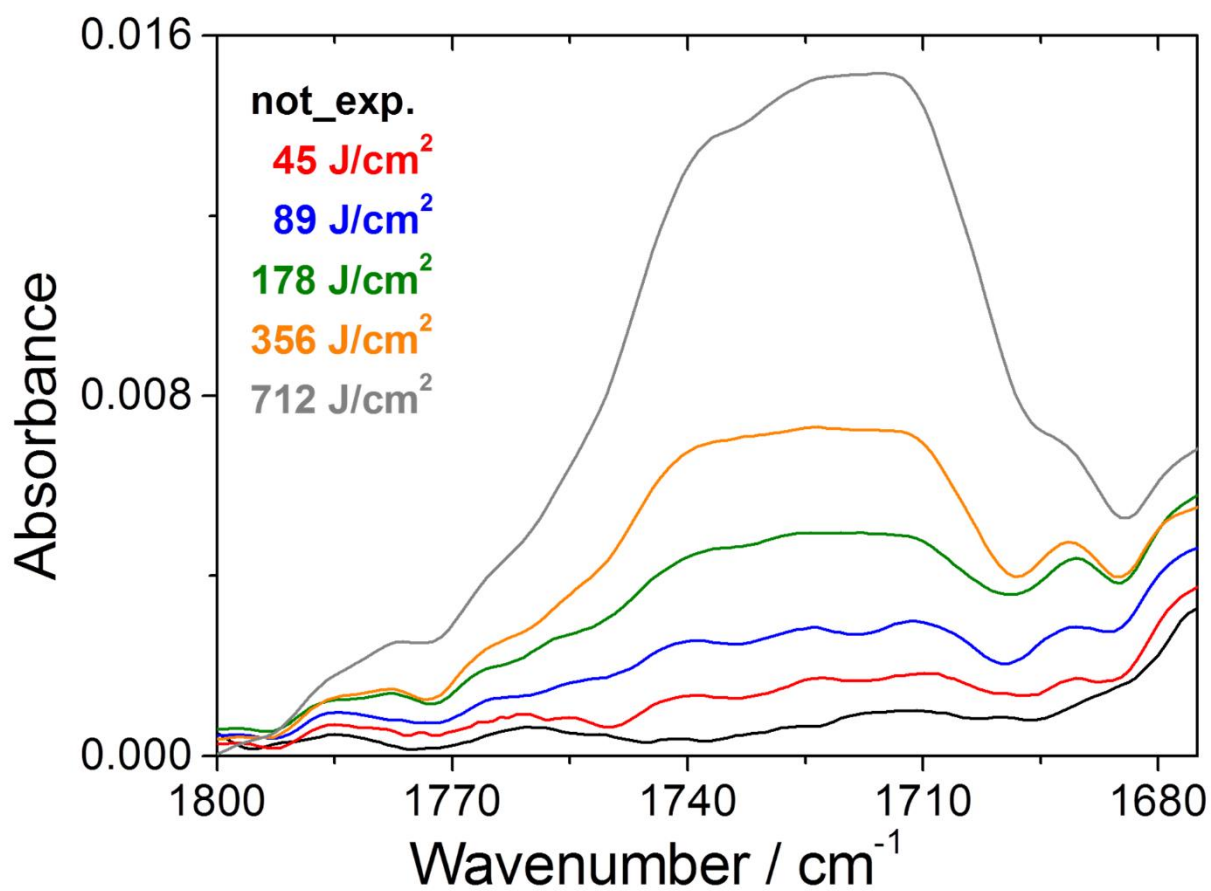


Figure S1 FTIR absorption spectra in the 1800–1675 cm⁻¹ range of the as-deposited ZnO films upon exposure to increasing X-ray doses.

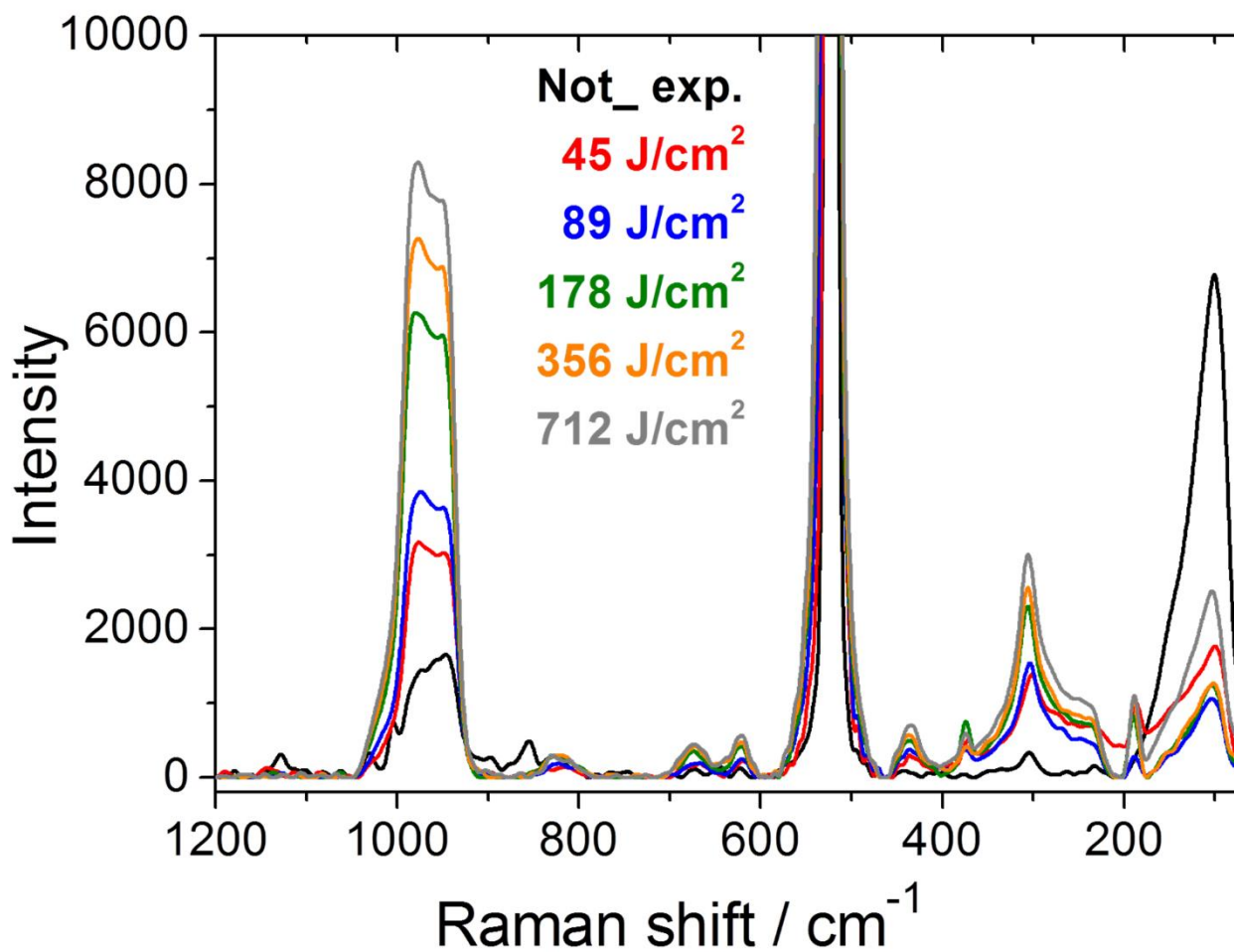


Figure S2 Raman spectra in the 1200 - 80 cm⁻¹ range of as-deposited films as a function of the exposure dose.

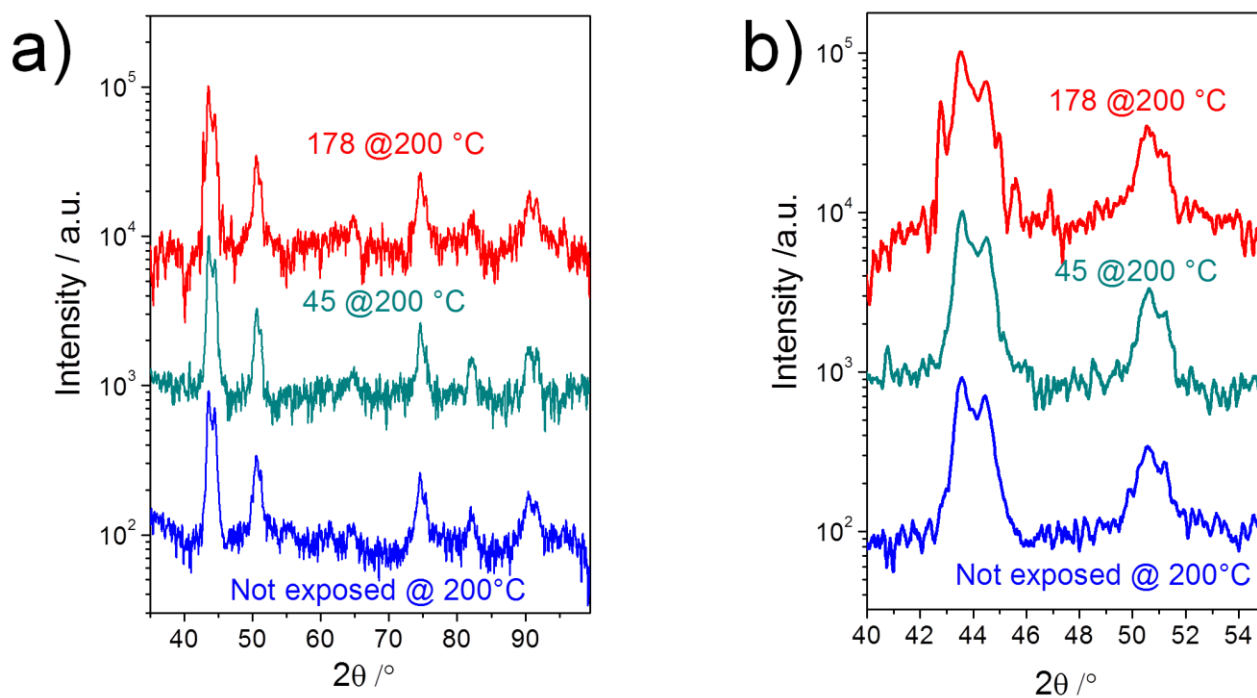


Figure S3 XRD patterns at increasing X-ray doses for films annealed at 200°C in the 35-99° and 40-53° 2θ range (a and b respectively).

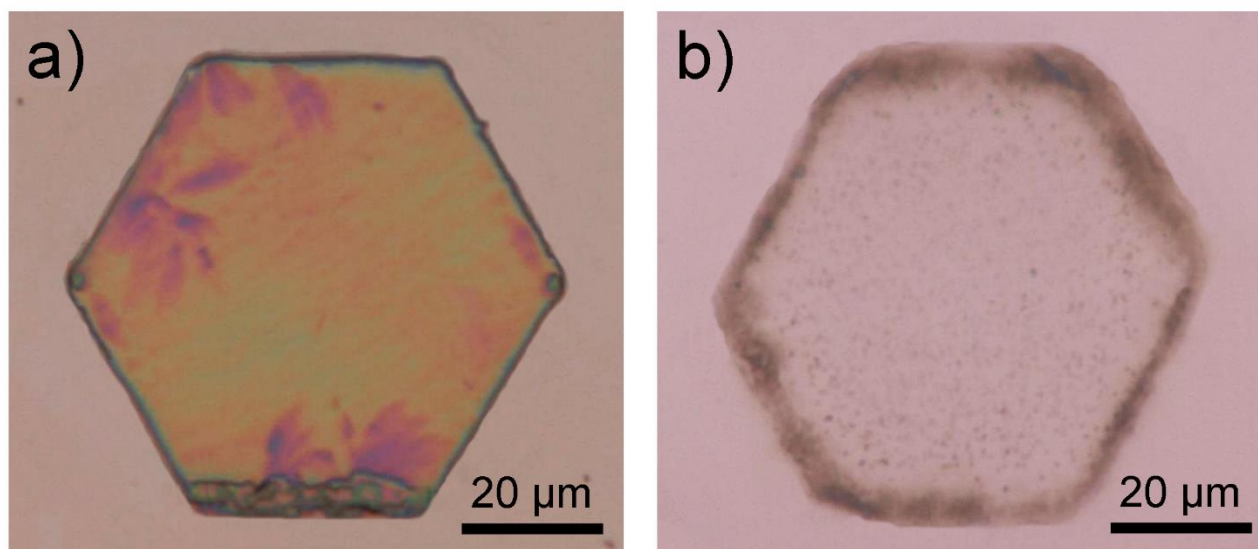


Figure S4 Optical images of a patterned film before and after thermal treatment at 300°C (a and b respectively).